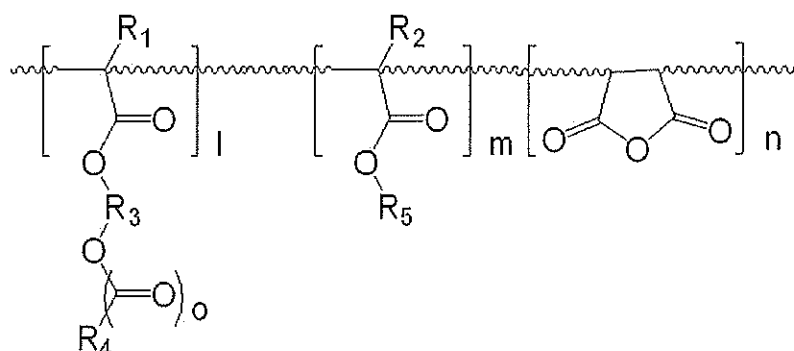


ADDITIVE FOR RESIST AND RESIST COMPOSITION COMPRISING SAME

ABSTRACT

A resist additive represented by Formula 1 below and a
 5 resist composition including the additive are disclosed.
 The resist additive contained in a resist composition
 improves hydrophobicity of the surface of a resist film
 during exposure to prevent leaching in water during immersion
 lithography and forms a micro resist pattern with excellent
 10 sensitivity and high resolution.

Formula 1



In Formula 1, the substituents are defined as
 described in the specification.